

Abstract:

Projection lens, in particular for microlithography
(Figure 1)

5 A projection lens (3), in particular for microlithography, is
provided with an object plane (7), with an image plane (9),
with a lens arrangement (4) and with at least one gas chamber
10 constructed as an approximately plane-parallel manipulation
chamber (13). The refractive index can be varied in the
manipulation chamber (13) by pressure changes and/or changes in
gas composition.

09847658-050201